

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	643	(polisilicon or conduct\$3) same (etch\$3 or pattern\$3) and (deep near reactive near ion near etch\$3 or "drie")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 16:18
L2	372	1 and (micromach\$3 or "MEMS")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 16:21
L3	21	2 and 216/2.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 16:22
S1	282357	(polisilicon or conduct\$3) same (etch\$3 or pattern\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 16:17
S2	313393	(polysilicon or conduct\$3) same (etch\$3 or pattern\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 13:40
S3	1086	S2 same (micromach\$3 or "MEMS")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 14:04
S4	185	S3 same (mirror or sensor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 13:41
S5	54	S4 and @pd<"20021024"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 13:41
S6	430	(micro near mirror) same (micromach\$3 or "MEMS")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 14:04

S7	116	S6 and S2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 14:13
S8	487	216/2.ccls. and S2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 14:14
S9	15	S8 and (second near insulat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/11 14:15
S10	15	kouma-norinao.in	US-PGPUB; USPAT	OR	OFF	2005/06/11 14:38